Author Index of Volume 235

Abass, A. K., 22
Abdel-Latif, R. M., 222
Adibi, F., 62
Alaoui, Z. K., 25
Arnell, R. D., 156
Auret, F. D., 163

Bai, G., 86
Bamberger, M., 142
Bange, K., 228
Barnard, W. O., 163
Bársony, I., 189
Basmaji, P., 234
Bernède, J. C., 25
Bestaoui, N., 35
Bhoraskar, S. V., 43
Bhuiyan, A. H., 43
Boas, M., 142
Bourget, L. P., 30
Brec, R., 35
Brzezinski, V., 116
Budniok, A., 96

Chang, H. L. M., 86
Chang, T.-S., 169
Chandhuri, A. K., 215
Chen, J.-R., 169
Chung, C.-S., 149
Collins, R. A., 22

Das, S., 215
Davis, R. F., 30
Deniard, P., 35
Djabella, H., 156

Edamura, T., 198
Effenberger, F., 210
El-Shabasy, M., 222

Faber, K. T., 137
Feile, R., 228
Feng, L., 76
Fort, A. F., 47
Froment, M., 51

Gao, Y., 86
Goerke, F., 202
Goto, K., 101
Greene, J. E., 62
Grivickas, V., 234
Grünewald, W., 57

Hamann, C., 57
Hayashi, Y., 101
Heilmann, A., 57
Hiraoka, K., 182
Homma, T., 80
Huang, F.-S., 169
Hultman, L., 62

Ichimura, K., 101
Ikeda, N., 71
Inoue, H., 10
Ishizuki, N., 101

Jordan, D. W., 137
Jou, J.-H., 149

Klappe, J. G. E., 189
Kobayashi, K., 20
Kunimune, K., 80
Kutsuzawa, Y., 80

Lahiri, S. K., 215
Lam, D. J., 86
Lau, E. H., 1
Lek, A. W., 1
Li, H. M., 1
Li, R., 210
Liefting, J. R., 189
Lipiński, A., 13
Liu, J., 76
Loïzos, Z., 51

Manai, N., 25
Matsubara, T., 20
Matsushima, S., 20
Matyja, P., 96
Maurin, G., 51
Merkle, K. L., 86
Merkt, U., 202
Meyer, W. E., 163
Mitsis, A., 51
Murao, Y., 80
Muto, J., 198
Myburg, G., 163
Mycielski, W., 13

Nalwa, H. S., 13
Niesert, C.-P., 210

Okada, G., 20
Okitsu, K., 10
Oleksy, M., 96
Ottermann, C., 228
O'Neill, D., 120, 129

Paisley, M. J., 30
Pan, X., 112
Peterson, I. R., 116
Petrov, I., 62
Prouzet, E., 35

Radhakrishnan, K., 1
Rauch, F., 228
Reinhardt, C., 57
Riad, A. S., 222
Riaz, U., 15
Roth, S., 210
Ryan, T. W., 189

Sahu, S. C., 17
Sahu, S. N., 17
Sato, M., 71
Schilling, M., 202
Schmelzer, M., 210
Selverian, J. H., 120, 129
Sparks, D. R., 108
Spyrellis, N., 51
Staryga, E., 13
Sugimoto, A., 10
Sundgren, J.-E., 62

Tawara, H., 71
Tsunooka, M., 10

Uehara, K., 10

Varkey, A. J., 47

Wagner, W., 228
Wahlström, U., 62
Wang, W.-C., 169

Yamazaki, T., 71
Yoon, S. F., 1

Zhang, D. H., 1
Zhao, D., 112
Zou, J., 6

Subject Index of Volume 235

Aluminium
  chemically-accelerated corrosion tests for aluminum metallized ICs, 108
  effect of temperature on stress-induced open failure in aluminum interconnects of LSIs, 182
  mechanical characteristics of aluminum thin films on silicon and gallium arsenide, 149
Amorphous materials
  persistent photoconductivity and band offset in μc-Si:H/a-Si:H superlattices, 76
  structural and analytical characterization of an iridium oxide thin layer, 35
Anisotropy
  magnetic alignment of aliphatic lamellae, 116
  photocontrol of in-plane alignment of a nematic liquid crystal by a photochromic spiropyran molecular layer, 101
Annealing
  optimization of ion implantation damage annealing by means of high-resolution X-ray diffraction, 189
Auger electron spectroscopy
  electrical and surface properties of thin film of Li glass solid electrolyte, 112

Boron nitride
  boron nitride thin films by microwave ECR plasma chemical vapor deposition, 30

Cadmium
  electrodeposition and properties of copper-doped cadmium sulphide, 198
Cadmium selenide
  cadmium chalcogenide semiconducting thin films prepared by electrodeposition from boiling aqueous electrolytes, 51
Cadmium telluride
  cadmium chalcogenide semiconducting thin films prepared by electrodeposition from boiling aqueous electrolytes, 51
Carbides
  structural characterization of laser-processed WC/Co layers, 142
Ceramics
  finite element comparative study of elastic stresses in single, double layer and multilayered coated systems, 156
Chemical vapour deposition
  boron nitride thin films by microwave ECR plasma chemical vapor deposition, 30
  strength and toughness measurement of thin brittle coatings on substrates. Part II. Experimental determination, 129
Coatings
  magnetic alignment of aliphatic lamellae, 116
  X-ray residual stress analysis of a ceramic thermal barrier coating undergoing thermal cycling, 137
Computer simulation
  effect of temperature on stress-induced open failure in aluminum interconnects of LSIs, 182
  finite element comparative study of elastic stresses in single, double layer and multilayered coated systems, 56
Conductivity
  d.c. electrical measurements and temperature dependence of the Schottky barrier capacitance on thin films of β-MgPc dispersed in polycarbonate, 222
Contacts
  diffusion barrier study on $TaSi_x$ and $TaSi_xN_y$, 169
  effect of electron-beam deposition rate on the electrical properties of Ti/ and Pt/n-GaAs contacts, 163
Copper
  electrodeposition and properties of copper-doped cadmium sulphide, 198
  investigations of the microstructure of plasma polymer tin and copper composite films using electron microscopy methods, 57
Corrosion
  chemically-accelerated corrosion tests for aluminum metallized ICs, 108

Deposition process
  finite element comparative study of elastic stresses in single, double layer and multilayered coated systems, 156
  invstigation of composition uniformity of $MoSi_x$ sputtering films based on measurement of angular distribution of sputtered atoms, 71
  laser deposition of epitaxial $YBa_2Cu_3O_7$ films with low droplet densities, 202
Dielectric properties
  electrical and surface properties of thin film of Li glass solid electrolyte, 112
Dielectrics
  effects of substrate orientation and cooling rate on microstructure of $PbTiO_3$ thin films grown by metal-organic chemical vapour deposition, 86
  stability of a new polyimide siloxane film as interlayer dielectrics of ULSI multilevel interconnections, 80
Diffusion
  diffusion barrier study on $TaSi_x$ and $TaSi_xN_y$, 169
  microstructural and electrical characterisation of ion-beam-sputtered polysilicon films for microelectronic applications, 215

Electrical properties and measurements
  d.c. electrical measurements and temperature dependence of the Schottky barrier capacitance on thin films of β-MgPc dispersed in polycarbonate, 222
  effect of electron-beam deposition rate on the electrical properties of Ti/ and Pt/n-GaAs contacts, 163
  electrical and surface properties of thin film of Li glass solid electrolyte, 112
  electrodeposition and properties of copper-doped cadmium sulphide, 198
Electrochemistry
  cadmium chalcogenide semiconducting thin films prepared by electrodeposition from boiling aqueous electrolytes, 51
  electrolytic composite layers based on nickel with nickel oxide addition, 96
Electron diffraction
  magnetic alignment of aliphatic lamellae, 116
Electron microscopy
  investigations of the microstructure of plasma polymer tin and copper composite films using electron microscopy methods, 57
  optical absorption in porous silicon of high porosity, 234

Gallium arsenide
mechanical characteristics of aluminum thin films on silicon and gallium arsenide, 149
Gold
chemically-accelerated corrosion tests for aluminum metallized ICs, 108
Grain boundary
microstructural and electrical characterisation of ion-beam-sputtered polysilicon films for microelectronic applications, 215

Interfaces
photocontrol of in-plane alignment of a nematic liquid crystal by a photochromic spiropyran molecular layer, 101
Ion bombardment
compaction of tungsten oxide films by ion-beam irradiation, 228
microstructural and electrical characterisation of ion-beam-sputtered polysilicon films for microelectronic applications, 215
Ion implantation
optimization of ion implantation damage annealing by means of high-resolution X-ray diffraction, 189
Iridium
structural and analytical characterization of an iridium oxide thin layer, 35

Langmuir–Blodgett films
highly ordered LB films of DHAP: a donor acceptor substituted polyene, 210
Laser ablation
laser deposition of epitaxial $YBa_2Cu_3O_7$ films with low droplet densities, 202
Laser irradiation
structural characterization of laser-processed WC/Co layers, 142
third-order non-linear optical susceptibility measurements of thin films of 3-methylthiophene and methylmethacrylate copolymers, 175

Metallization
diffusion barrier study on $TaSi_x$ and $TaSi_xN_y$, 169
effect of electron-beam deposition rate on the electrical properties of Ti/ and Pt/n-GaAs contacts, 163
Molybdenum oxide
films of molybdenum trioxide obtained from $MoTe_2$ oriented films, 25
Monolayers
photocontrol of in-plane alignment of a nematic liquid crystal by a photochromic spiropyran molecular layer, 101

Nickel
electrolytic composite layers based on nickel with nickel oxide addition, 96
Nickel oxide
electrolytic composite layers based on nickel with nickel oxide addition, 96

Optical coatings
compaction of tungsten oxide films by ion-beam irradiation, 228
Optical properties
third-order non-linear optical susceptibility measurements of thin films of 3-methylthiophene and methylmethacrylate copolymers, 175
Organic substances
d.c. electrical measurements and temperature dependence of the Schottky barrier capacitance on thin films of β-MgPc dispersed in polycarbonate, 222
highly ordered LB films of DHAP: a donor acceptor substituted polyene, 210
magnetic alignment of aliphatic lamellae, 116
photocontrol of in-plane alignment of a nematic liquid crystal by a photochromic spiropyran molecular layer, 101
Organometallic vapour deposition
effects of substrate orientation and cooling rate on microstructure of $PbTiO_3$ thin films grown by metal-organic chemical vapour deposition, 86
Oxidation
films of molybdenum trioxide obtained from $MoTe_2$ oriented films, 25

Phase transitions
crystal growth and microstructure of polycrystalline $Ti_{1-x}Al_xN$ alloy films deposited by ultra-high-vacuum dual-target magnetron sputtering, 62
Photoconductivity
persistent photoconductivity and band offset in μc-Si:H/a-Si:H superlattices, 76
Physical vapour deposition
X-ray residual stress analysis of a ceramic thermal barrier coating undergoing thermal cycling, 137
Planarization
stability of a new polyimide siloxane film as interlayer dielectrics of ULSI multilevel interconnections, 80
Plasma processing and deposition
evidence of the formation of a charge-transfer complex between iodine and plasma-polymerized acrylonitrile, 43
investigations of the microstructure of plasma polymer tin and copper composite films using electron microscopy methods, 57
Polymers
stability of a new polyimide siloxane film as interlayer dielectrics of ULSI multilevel interconnections, 80
third-order non-linear optical susceptibility measurement of thin films of 3-methylthiophene and methylmethacrylate copolymers, 175
Pyrolysis
evidence of the formation of a charge-transfer complex between iodine and plasma-polymerized acrylonitrile, 43

Quantum effects
optical absorption in porous silicon of high porosity, 234

Radiation damage
compaction of tungsten oxide films by ion-beam irradiation, 228
Reffection spectroscopy
optical absorption in porous silicon of high porosity, 234
Rutherford backscattering spectroscopy
investigation of composition uniformity of $MoSi_x$ sputtering films based on measurement of angular distribution of sputtered atoms, 71

Scanning electron microscopy
electrical and surface properties of thin film of Li glass solid electrolyte, 112
laser deposition of epitaxial $YBa_2Cu_3O_7$ films with low droplet densities, 202

Schottky barrier
d.c. electrical measurements and temperature dependence of the Schottky barrier capacitance on thin films of β-MgPc dispersed in polycarbonate, 222
effect of electron-beam deposition rate on the electrical properties of Ti/ and Pt/n-GaAs contacts, 163
Second harmonic generation
third-order non-linear optical susceptibility measurements of thin films of 3-methylthiophene and methylmethacrylate copolymers, 175
Semiconductors
cadmium chalcogenide semiconducting thin films prepared by electrodeposition from boiling aqueous electrolytes, 51
effect of temperature on stress-induced open failure in aluminum interconnects of LSIs, 182
stability of a new polyimide siloxane film as interlayer dielectrics of ULSI multilevel interconnections, 80
Silicides
diffusion barrier study on $TaSi_x$ and $TaSi_xN_y$, 169
investigation of composition uniformity of $MoSi_x$ sputtering films based on measurement of angular distribution of sputtered atoms, 71
Silicon
chemically-accelerated corrosion tests for aluminum metallized ICs, 108
mechanical characteristics of aluminum thin films on silicon and gallium arsenide, 149
optical absorption in porous silicon of high porosity, 234
Sputtering
crystal growth and microstructure of polycrystalline $Ti_{1-x}Al_xN$ alloy films deposited by ultra-high-vacuum dual-target magnetron sputtering, 62
investigation of composition uniformity of $MoSi_x$ sputtering films based on measurement of angular distribution of sputtered atoms, 71
Stress
effect of temperature on stress-induced open failure in aluminum interconnects of LSIs, 182
finite element comparative study of elastic stresses in single, double layer and multilayered coated systems, 156
mechanical characteristics of aluminum thin films on silicon and gallium arsenide, 149
strength and toughness measurement of thin brittle coatings on substrates. Part I. Theory and measurement, 120
strength and toughness measurement of thin brittle coatings on substrates. Part II. Experimental determination, 129
X-ray residual stress analysis of a ceramic thermal barrier coating undergoing thermal cycling, 137
Structural properties
crystal growth and microstructure of polycrystalline $Ti_{1-x}Al_xN$ alloy films deposited by ultra-high-vacuum dual-target magnetron sputtering, 62
highly ordered LB films of DHAP: a donor acceptor substituted polyene, 210
Superconductivity
laser deposition of epitaxial $YBa_2Cu_3O_7$ films with low droplet densities, 202
Superlattices
persistent photoconductivity and band offset in μc-Si:H/a-Si:H superlattices, 76
Surface composition
evidence of the formation of a charge-transfer complex between iodine and plasma-polymerized acrylonitrile, 43

Tellurium
films of molybdenum trioxide obtained from $MoTe_2$ oriented films, 25
Tin
investigations of the microstructure of plasma polymer tin and copper composite films using electron microscopy methods, 57
Titanium nitride
crystal growth and microstructure of polycrystalline $Ti_{1-x}Al_xN$ alloy films deposited by ultra-high-vacuum dual-target magnetron sputtering, 62
strength and toughness measurement of thin brittle coatings on substrates. Part II. Experimental determination, 129
Transmission electron microscopy
effects of substrate orientation and cooling rate on microstructure of $PbTiO_3$ thin films grown by metal-organic chemical vapour deposition, 86
Tungsten
structural characterization of laser-processed WC/Co layers, 142
Tungsten oxide
compaction of tungsten oxide films by ion-beam irradiation, 228

X-ray absorption
structural and analytical characterization of an iridium oxide thin layer, 35
X-ray diffraction
effects of substrate orientation and cooling rate on microstructure of $PbTiO_3$ thin films grown by metal-organic chemical vapour deposition, 86
electrolytic composite layers based on nickel with nickel oxide addition, 96
films of molybdenum trioxide obtained from $MoTe_2$ oriented films, 25
microstructural and electrical characterisation of ion-beam-sputtered polysilicon films for microelectronic applications, 215
optimization of ion implantation damage annealing by means of high-resolution X-ray diffraction, 189
structural and analytical characterization of an iridium oxide thin layer, 35
structural characterization of laser-processed WC/Co layers, 142
X-ray residual stress analysis of a ceramic thermal barrier coating undergoing thermal cycling, 137
X-ray photoelectron spectroscopy
evidence of the formation of a charge-transfer complex between iodine and plasma-polymerized acrylonitrile, 43
persistent photoconductivity and band offset in μc-Si:H/a-Si:H superlattices, 76